

EXAMINER INITIALS	Cite No.	DOCUMENT NUMBER Number-Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where, Relevant Passages or Relevant Figures Appear
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	A14					·
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EXAMINER		NON PATENT LITERATURE DOCUMENTS			
INITIAL	(Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.				
/WL/	A18	C. Youtsey, G. Bulman and I. Adesida, Dopant-Selective Photoenhanced Wet Etching of GaN, Journal of Electronic Materials, Vol. 27, No. 4, 1998, Microelectronics Laboratory and Department of Electrical and Computer Engineering, Univ. of Illinois, Urbana, IL 61801, CREE Research, Inc. Durham, NC 27713.			
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V	A20	C. Bieth et al., Recent Development in ECR Sources, Nukleonika 2003; 48 (Supplement 2); S93-S98.			
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